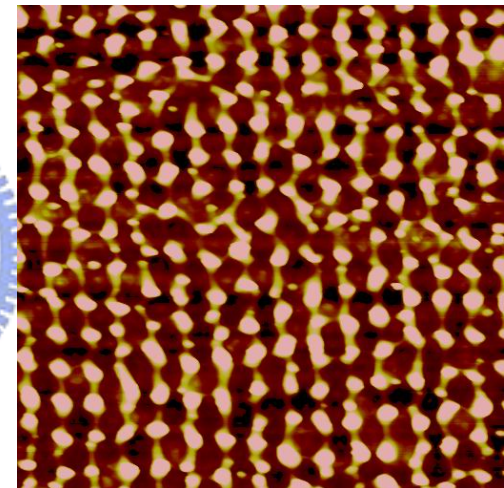
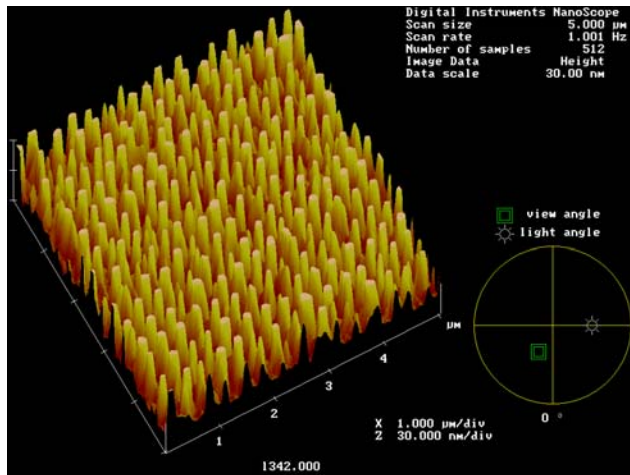
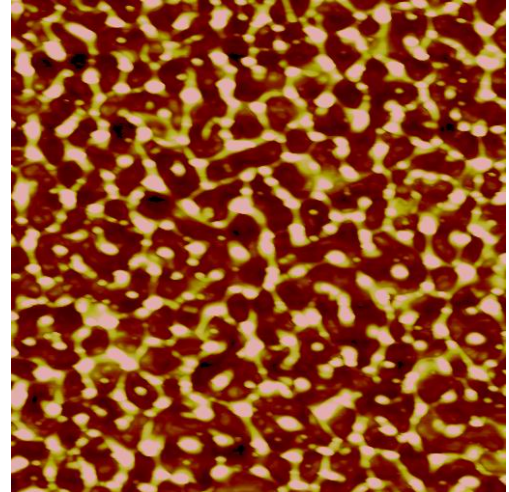
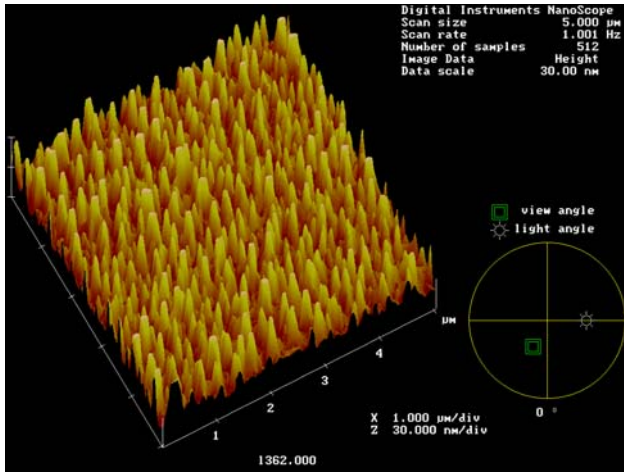


(a)



(b)

**Fig. 3-32** AFM micrographs of excimer laser crystallized poly-Silicon films surface roughness. The applied laser energy densities are (a) 300, (b) 340 mJ/cm<sup>2</sup> in the O<sub>2</sub> ambience with concentration 2000 ppm. The laser energy 950 mJ, frequency 300 Hz, power 285 W, scan speed 6 mm/sec, pitch 0.02 mm, beam width 0.4 mm, pre treatment clean with HF 1% for 30 sec



(c)

**Fig. 3-32** AFM micrographs of excimer laser crystallized poly-Silicon films surface roughness. The applied laser energy densities are (c)  $360 \text{ mJ/cm}^2$  in the  $\text{O}_2$  ambiance with concentration 2000ppm. The laser energy 950mJ, frequency 300Hz, power 285W, scan speed 6mm/sec, pitch 0.02mm, beam width 0.4mm, pre treatment clean with HF 1% for 30sec

